

IN THE CLAIMS:

Please AMEND the claims as indicated below:

1-30. (CANCELED)

31. (CURRENTLY AMENDED) A method comprising:

forming, on a substrate having an error of shape, a multilayer film stack of alternating layers of high refractive index material and low refractive index material and that reflects radiation in a range from vacuum ultraviolet through X-ray; and

cutting away at least one cycle of alternating layers from a portion of the multilayer film stack so that the multilayer film stack, having said at least one cycle cut away, corrects a wavefront aberration ~~controls the error of shape of the substrate in accordance with an amount of adjustment of a wavefront phase of a light reflected by the multilayer film stack that would have been caused by the error of shape of the substrate if said at least one cycle of alternating layers were not cut away.~~

32. (PREVIOUSLY PRESENTED) The method according to claim 31, wherein the multilayer film stack is formed in a number of cycles of alternating layers of high refractive index material and low refractive index material larger than that necessary to saturate a reflectance.

33. (PREVIOUSLY PRESENTED) The method according to claim 31, wherein said cutting away is controlled by detecting a difference in a material that forms the multilayer film stack.

34. (PREVIOUSLY PRESENTED) The method according to claim 33, wherein a difference in material is detected by monitoring a secondary electron discharge.

35. (PREVIOUSLY PRESENTED) The method according to claim 33, wherein a difference in material is detected by monitoring an optical change of characteristics.

36. (PREVIOUSLY PRESENTED) The method according to claim 35, wherein said optical change of characteristics monitored is a change in an optical constant of visible rays or a change based on ellipsometry.

37. (PREVIOUSLY PRESENTED) A method for forming an optical element that reflects radiation in a range from vacuum ultraviolet through X-ray, comprising:

forming on a substrate a multilayer film having a stack of alternating layers of high refractive index material and low refractive index material in a number of cycles larger than necessary to saturate reflectance;

forming a correction film on the multilayer film; and

cutting away a portion of the correction film and the multilayer film stack in accordance with an amount of adjustment of a wavefront phase of emerging rays.

38. (CURRENTLY AMENDED) A multilayer film reflection mirror that reflects radiation in a range from vacuum ultraviolet through X-ray comprising:

a substrate having an error of shape; and

a multilayer film formed on the substrate for reflecting the radiation, wherein the multilayer film is formed by a plurality of repeated pairs of layers, layers of each pair of layers having different refractive indexes from each other, at least one pair of layers successively arranged from an outermost surface of the multilayer film having a predetermined portion in which material of the respective layers of the respective pair does not exist so that the respective layers are thereby non-uniform across the multilayer film, and so that the multilayer film thereby ~~corrects a wavefront aberration~~ ~~controls the error of shape of the substrate in accordance with an amount of adjustment of a wavefront phase of a light reflected by the multilayer film that would have been caused by the error of shape of the substrate if said at least one pair of layers successively arranged from the outermost surface of the multilayer film did not have said predetermined portion.~~

39. (CURRENTLY AMENDED) The multilayer film reflection mirror according to claim 38, wherein said wavefront ~~aberration is corrected~~ ~~phase is adjusted~~ with more than one layer among said plurality of repeated pairs.

40. (CANCELED)

41. (CANCELED)

42. (PREVIOUSLY PRESENTED) The multilayer film reflection mirror according to claim 38, wherein the multilayer film is formed by repeated pairs of layers whose number exceeds a number at which reflectivity is substantially saturated.

43. (CURRENTLY AMENDED) The multilayer film reflection mirror according to claim 42, wherein the ~~wavefront aberration is corrected~~ ~~error of shape of the substrate is controlled~~ with

more than one layer among the pairs of layers where the reflectivity is already saturated being partially removed.

44. (PREVIOUSLY PRESENTED) The multilayer film reflection mirror according to claim 42, wherein reflectivity of said multilayer film is between about 15% and about 80%.

45. (PREVIOUSLY PRESENTED) The multilayer film reflection mirror according to claim 38, wherein said light is an EUV light.

46. (PREVIOUSLY PRESENTED) The multilayer film reflection mirror according to claim 38, wherein said multilayer film is formed by pairs of molybdenum and silicon layers.

47. (CURRENTLY AMENDED) The multilayer film reflection mirror according to claim 38, wherein said multilayer film is one-of-a multilayer film formed by pairs of ruthenium and silicon layers, a multilayer film formed by pairs of rhodium and silicon layers, a multilayer film formed by pairs of ruthenium and carbon layers, or a multilayer film formed by pairs of rhodium and carbon layers.

48. (CURRENTLY AMENDED) An exposure apparatus comprising:
a mirror comprising:

a substrate having an error of shape; and
a multilayer film formed on the substrate and reflecting radiation in a range from vacuum ultraviolet through X-ray, the multilayer film formed by a plurality of repeated pairs of layers, layers of each pair of layers having different refractive indexes from each other, at least one repeated pair of layers successively arranged from an outermost surface of the multilayer film having a predetermined portion in which material of the respective layers does not exist so that the respective layers are thereby non-uniform across the multilayer film and so that the multilayer film thereby corrects a wavefront aberration ~~controls the error of shape of the substrate in accordance with an amount of adjustment of a wavefront phase of a light reflected by the multilayer film that would have been caused by the error of shape of the substrate if said at least one repeated pair of layers successively arranged from the outermost surface of the multilayer film did not have said predetermined portion.~~

49. (CURRENTLY AMENDED) A method of manufacturing a multilayer film reflection

mirror, comprising:

forming a substrate having an error of shape; and

forming a multilayer film on the substrate, the multilayer film having a plurality of repeated pairs of layers and reflecting radiation in a range from vacuum ultraviolet through X-ray, each pair of layers having layers with different refractive indexes from each other, at least one pair of layers successively arranged from an outermost surface of the multilayer film having a predetermined portion in which material of the respective layers does not exist so that the respective layers are thereby non-uniform across the multilayer film, so that the multilayer film thereby corrects a wavefront aberration ~~and controls the error of shape of the substrate in accordance with an amount of adjustment of a wavefront phase of a light reflected by the multilayer film that would have been caused by the error of shape of the substrate if said at least one pair of layers successively arranged from the outermost surface of the multilayer film did not have said predetermined portion.~~

50. (PREVIOUSLY PRESENTED) The method according to claim 49, further comprising partially removing at least one layer among said plurality of repeated pairs of layers, to thereby provide said at least one pair of layers successively arranged from an outermost surface of the multilayer film having a predetermined portion in which material of the respective layers does not exist.

51. (PREVIOUSLY PRESENTED) The method according to claim 50, wherein the removing of the multilayer film is stopped at a portion of a layer having a relatively higher refractive index among said layers in a pair having different refractive indexes from each other.

52. (PREVIOUSLY PRESENTED) The method according to claim 51, wherein said layer having a relatively higher refractive index is made of silicon.

53. (PREVIOUSLY PRESENTED) The method according to claim 49, wherein said multilayer film is formed by repeated pairs whose number exceeds a number at which reflectivity substantially is saturated.

54. (PREVIOUSLY PRESENTED) The method according to claim 53, further comprising partially removing more than one layer among the pairs of layers of the multilayer film where the reflectivity is already saturated, to thereby provide said at least one pair of layers successively arranged from an outermost surface of the multilayer film having a predetermined

portion in which material of the respective layers does not exist.

55. (PREVIOUSLY PRESENTED) The method according to claim 53, wherein reflectivity of said multilayer film is between about 15% and about 80%.

56. (PREVIOUSLY PRESENTED) The method according to claim 49, wherein said light is an EUV light.

57. (PREVIOUSLY PRESENTED) The method according to claim 49, wherein said multilayer film is made from molybdenum and silicon layers.

58. (CURRENTLY AMENDED) The method according to claim 49, wherein said multilayer film is one of a multilayer film formed with pairs of ruthenium and silicon layers, a multilayer film formed with pairs of rhodium and silicon layers, a multilayer film formed with pairs of ruthenium and carbon layers, or a multilayer film formed with pairs of rhodium and carbon layers.

59. (CURRENTLY AMENDED) An optical element comprising:
a substrate having an error of shape;
a multilayer film formed on the substrate, the multilayer film having a stack of alternating layers of high refractive index material and low refractive index material in a number of cycles larger than necessary to saturate reflectance; and
a correction film on the multilayer film,
wherein the multilayer film reflects radiation in a range from vacuum ultraviolet through X-ray, and the correction film and the stack each have a cut away portion with at least one cycle of alternating layers being cut away in the cut away portion of the multilayer film stack, so that the stack having said cut away portion corrects a wavefront aberration~~the error shape of the substrate is controlled in accordance with an amount of adjustment of a wavefront phase of a light reflected by the multilayer film~~ that would have been caused by the error of shape of the substrate if the stack did not have said cut away portion.

60. (CURRENTLY AMENDED) A multilayer film reflection mirror comprising:
a substrate having an error of shape; and

a multilayer film formed on the substrate and reflecting radiation in a range from vacuum ultraviolet through X-ray, wherein the error of shape of the substrate is controlled by at least one cycle of a predetermined portion of the multilayer film corrects a wavefront aberration in accordance with an amount of adjustment of a wavefront phase of a light reflected by the multilayer film that would have been caused by the error of shape of the substrate if said at least one cycle did not make a correction.